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13.5nm, 25.4mm Dia, 5° AOI, EUV Flat Mirror

Extreme Ultraviolet (EUV) Flat Mirrors

Stock **#38-759** **10 In Stock**

- 1 + **C$3,850.00**

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Qty 1+	**C$3,850.00** each
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General

Type:
Flat Mirror

Physical & Mechanical Properties

Diameter (mm):
25.40 ±0.25

Thickness (mm):
6.35 ±0.508

Back Surface:
Commercial Polish

Clear Aperture (%):	90
Edges:	Fine Ground
Parallelism (arcmin):	3
Surface Roughness (□):	<5 RMS

Optical Properties

Coating Type:	Metal/Semiconductor
Coating:	Mo/Si Multilayer Top Layer: Silicon
Surface Flatness (P-V):	λ/10 @ 632.8nm
Wavelength Range (nm):	13.18 - 13.68
Design Wavelength DWL (nm):	13.5
Substrate: □	Single Crystal Silicon
Angle of Incidence (°):	5
Coating Specification:	R_{abs} >60% @ 13.5nm, 5° (s-pol)
Surface Quality:	10-5
Reflection at DWL (%):	>60
Full Width-Half Max FWHM (nm):	0.50

Electrical

Center Energy (eV):	92

Regulatory Compliance

Certificate of Conformance:	View

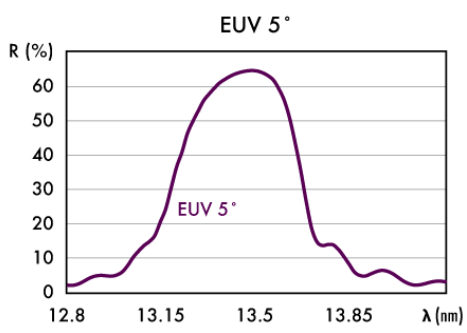
Product Details

- Maximum Achievable Reflection at 13.5nm
- Designed for EUV Beam Steering and Harmonic Separation
- 5° and 45° AOI Versions Available

Extreme Ultraviolet (EUV) Flat Mirrors are multilayer mirrors designed for maximum achievable reflectance at the design wavelength and angle of incidence. These mirrors feature a coating deposited on a super-polished single crystal silicon substrate and surface roughness less than 3□ RMS. The 45° AOI mirrors are useful for steering s-polarized beams, while the 5° AOI mirrors may be used with unpolarized beams. Applications for EUV mirrors include Coherent Diffractive Imaging (CDI) and materials science research. Extreme Ultraviolet (EUV) Flat Mirrors can also serve as harmonic selectors for High Harmonic Generation (HHG) beams.

Note: Test data from each mirror's production run sample included.

Technical Information



Compatible Mounts

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